

Title (en)
SULFONIUM SALT, PHOTOACID GENERATOR, AND PHOTSENSITIVE COMPOSITION

Title (de)
SULFONIUMSALZ, FOTOSÄUREGENERATOR UND LICHTEMPFLINDLICHE ZUSAMMENSETZUNG

Title (fr)
SEL DE SULFONIUM, GÉNÉRATEUR PHOTO-ACIDE, ET COMPOSITION PHOTOSENSIBLE

Publication
EP 3199520 A4 20170927 (EN)

Application
EP 15843379 A 20150925

Priority
• JP 2014197335 A 20140926
• JP 2015077196 W 20150925

Abstract (en)
[origin: EP3199520A1] Provided are a novel sulfonium salt having high sensitivity with respect to active energy rays, a photoacid generator comprising the sulfonium salt, and a photosensitive composition containing the photoacid generator. The sulfonium salt is represented by formula (a1). In the formula, R 1 and R 2 each independently represent the group that is represented by formula (a2) or an alkyl group that may be substituted by a halogen atom, R 1 and R 2 are bonded to each other and may form a ring with the sulfur atom within the formula, R 3 is the group represented by formula (a3) or the group represented by formula (a4), A 1 represents S or the like, X - represents a monovalent anion, and R 1 and R 2 are not both an alkyl group which may be substituted with a halogen atom. In formulas (a2) to (a4), the ring Z 1 represents an aromatic hydrocarbon ring, R 4 , R 6 , R 9 , and R 10 each represents a specific monovalent group, R 5 , R 7 , and R 8 each represents a specific divalent group, A 2 and A 3 each represents S or the like, m1 represents an integer of 0 or more, and n1 and n2 each represent 0 or more.

IPC 8 full level
C07C 381/12 (2006.01); **C07C 309/06** (2006.01); **C09K 3/00** (2006.01); **G03F 7/004** (2006.01); **G03F 7/038** (2006.01); **G03F 7/039** (2006.01)

CPC (source: EP KR US)
C07C 309/06 (2013.01 - EP US); **C07C 321/28** (2013.01 - KR); **C07C 381/12** (2013.01 - EP US); **C09K 3/00** (2013.01 - EP US); **G03F 7/004** (2013.01 - KR); **G03F 7/0045** (2013.01 - EP US); **G03F 7/0046** (2013.01 - US); **G03F 7/0382** (2013.01 - EP US); **G03F 7/039** (2013.01 - KR US); **G03F 7/0392** (2013.01 - EP US); **G03F 7/0397** (2013.01 - EP US); **G03F 7/2004** (2013.01 - US); **G03F 7/322** (2013.01 - US)

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Designated contracting state (EPC)
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EP 3199520 A1 20170802; EP 3199520 A4 20170927; EP 3199520 B1 20191225; CN 107074759 A 20170818; CN 107074759 B 20211214; CN 113264856 A 20210817; CN 113264856 B 20221122; JP 2020143082 A 20200910; JP 6700188 B2 20200527; JP 6865318 B2 20210428; JP WO2016047784 A1 20170713; KR 102421321 B1 20220718; KR 20170065560 A 20170613; TW 201627280 A 20160801; TW I673258 B 20191001; US 10059662 B2 20180828; US 2017305848 A1 20171026; WO 2016047784 A1 20160331

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